Serial No. 09/966,958 Filing Date 09/28/2001 Customer No. 26,289 Attorney Docket 2001US307

## Complete Set of Claims

- 1. (Currently Amended) A negative aqueous photoresist composition, comprising:
- a) a polymer comprising at least one unit with structure (1)

where  $R_1$  is hydrogen or  $(C_1-C_4)$  alkyl and n = 1-4;

- b) a water-soluble photoactive compound;
- c) a crosslinking agent; and,
- d) a solvent composition—, and further where the photoactive compound has structure (2).

$$(R_2)_{\overline{m}}$$
 OCH<sub>3</sub> (2)

where,

 $R_2$  is hydrogen, alkyl. -O(alkyl), -(alkyl)OH, hydroxyphenyl or multihydroxyphenyl,  $R_3$  and  $R_4$  are independently ( $C_1$ - $C_4$ ) alkyl.

m = 1-3, and,

X is an anion.

2. (Delete)

Serial No. 09/966,958 Filing Date 09/28/2001 Customer No. 26,289 Attorney Docket 2001US307

- (Original) The photoresist composition according to claim 1, where solvent composition is water or a mixture of water and a (C<sub>1</sub>-C<sub>4</sub>) alkyl alcohol.
- 4. (Original) The photoresist composition according to claim 1, where the polymer contains additional nonaromatic units.
- 5. (Original) The photoresist composition according to claim 4, where the nonaromatic units are selected from a group consisting of ethylenic alcohol, ethylenic pyrollidone, ethylenic acetate, and methylene alcohol.
- 6. (Original) The photoresist composition according to claim 1, where the polymer contains at least 10 mole% of the unit of structure 1.
- 7. (Original) The photoresist composition according to claim 1, where n = 1 and  $R_1$  is selected from methyl, ethyl, propyl and butyl.
- 8. (Currently Amended) The photoresist composition according to claim 2 1, where the photoactive compound is (4-methoxyphenyl)dimethylsufonium trifluoromethanesulfonate.
- 9. (Original) The photoresist composition according to claim 1, where the crosslinker is selected from melamine resins, urea resins and glycolurils.
- 10. (Original) The photoresist composition according to claim 3, where the alcohol is isopropanol.
- 11. (Currently amended) A process for imaging a negative photoresist comprising the st ps of:

Serial No. 09/966,958 Filing Date 09/28/2001

Customer No. 26,289 Attorney Docket 2001US307

- a) forming on a substrate a photoresist coating from the photoresist composition of claim1;
- b) image-wise exposing the photoresist coating where the image-wise exposure wavelength is below 260nm;
- c) postexposure baking the photoresist coating; and
- d) developing the photoresist coating with a developer.
- 12. (Deleted)
- 13. (Original) The process according to claim 11, where the developer is selected from water, a mixture of water and a  $(C_1-C_4)$  alkyl alcohol, mixture of water and surfactant, and an aqueous base solution.
- 14. (Original) The process according to claim 13, where the alcohol is isopropanol.